Resolution Enhancement Techniques In Optical Lithography (SPIE Tutorial Texts In Optical Engineering Vol. TT47)
This tutorial summarizes optical lithography enhancement research and development over the past 20 years. Discusses theoretical and practical aspects of commonly used techniques, including optical imaging and resolution, modified illumination, optical proximity correction, alternating and attenuating phase-shifting masks, selecting RETs, and second-generation RETs. Useful for students and practicing lithographers.

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